

Title (en)
FOCUSED SUBSTRATE ALTERATION.

Title (de)
VERÄNDERUNG EINES SUBSTRATS DURCH EINEN FOKUSSIERTEN STRAHL.

Title (fr)
ALTERATION FOCALISEE D'UN SUBSTRAT.

Publication
EP 0198908 A4 19870302 (EN)

Application
EP 85905575 A 19851025

Priority
• US 66525184 A 19841026
• US 76937085 A 19850826

Abstract (en)
[origin: WO8602774A1] Alteration of a precisely located site on a substrate (35) using apparatus that comprises: a) a focusable ion source (10); b) a lens (22) positioned to focus ions emitted by the source into an ion beam (124); c) a vacuum chamber (30) for containing the substrate site in the path of the ion beam; and d) a directed gas inlet (55) positioned to provide a localized supply of a substance at the site whereby the beam interacts with the substances to cause the alteration localized at the site. Methods of performing the alteration are also disclosed.

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H01J 37/317

IPC 8 full level
G03F 1/00 (2006.01); **H01J 37/317** (2006.01)

CPC (source: EP)
G03F 1/74 (2013.01); **H01J 37/3178** (2013.01)

Citation (search report)
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• See references of WO 8602774A1

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